

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	55	electroless\$2 and capping layer same silane	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 12:46
L2	1	electroless\$2 and capping layer same silane same (cobalt or co)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 12:47
L3	29	electroless\$2 and capping layer same silane and (cobalt or co)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 12:50
L4	2	electroless\$2 and capping layer same silane and (cobalt)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 12:59
L5	0	(plasma near2 chemical vapor deposition or pecvd) same capping layer same silane same cobalt	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:01
L6	4	(plasma near2 chemical vapor deposition or pecvd) same capping layer same silane and cobalt	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:01
L7	8	(plasma near2 chemical vapor deposition or pecvd) same capping layer and silane and cobalt	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:20
L8	16	capping layer same (silicon or silicide) same cobalt same (copper or Cu)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:12
L9	1	8 and silane	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:12
L10	229	(plasma near2 chemical vapor deposition or pecvd) same silane and cobalt	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:21
L11	16	(plasma near2 chemical vapor deposition or pecvd) same silane and cobalt and capping layer	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:21
L12	15	("20020036143" "5420072" "5447887" "5674787" "5695810" "5783483" "5824599" "6023100" "6228770" "6274932" "6352917").PN. OR ("6573606"). URP.N.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 13:26
L13	15	12 and (chemical vapor deposition or cvd)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 14:26
L14	772	(cobalt silicide or cosi) same (capping or barrier or passivation)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 14:27

L15	99	(cobalt silicide or cosi) same (capping or barrier or passivation) same (copper or cu)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 14:28
L16	15	(cobalt silicide or cosi) same (capping or barrier or passivation) same (copper or cu) same (chemical vapor deposition or \$2cvd)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 15:00
L17	0	"10749776"	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 15:00
L18	0	"10?749776"	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 15:00
L19	1	"10/749776"	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 15:21
L20	1	"5695810".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 15:21
S1	354	electroless\$2 same refractory and (carbon silicon or nitrogen or C or Si or N)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/01/18 16:15
S2	62	electroless\$2 same refractory same (carbon silicon or nitrogen or C or Si or N)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/01/18 16:16
S3	207	S1 and (chemical vapor deposition or \$2cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/01/18 16:16
S4	30	S2 and (chemical vapor deposition or \$2cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/01/18 16:16
S5	6	("20020084529" "20030176049" "5380560" "5695810" "5824599" "6197364").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/01/19 12:45